

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2001-240625

(43)Date of publication of application : 04.09.2001

(51)Int.Cl.

C08F220/28
 C08F220/06
 C08F220/18
 C08F222/06
 C08F232/08
 C08K 5/00
 C08L 33/14
 G03F 7/039
 H01L 21/027

(21)Application number : 2000-049549

(71)Applicant : TOSHIBA CORP
DAICEL CHEM IND LTD

(2)Date of filing : 25.02.2000

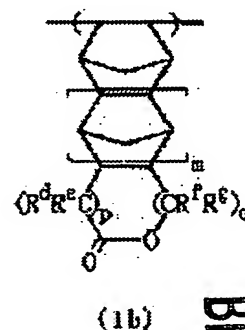
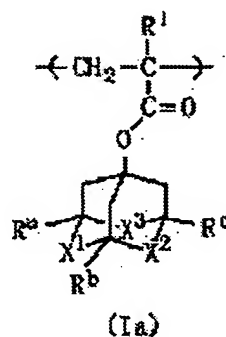
(72)Inventor : GOKOCHI TORU
OKINO TAKASHI
ASAKAWA KOUJI
SHINODA NAOMI
FUNAKI KATSUNORI
TSUTSUMI KIYOHARU
HORAI AKIRA

(54) POLYMER COMPOUND FOR PHOTORESIST AND PHOTORESIST RESIN COMPOSITION

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a polymer compound for photoresist excellent in adhesiveness to a substrate and capable of forming fine patterns in good accuracy.

SOLUTION: This polymer compound for photoresist contains at least one species of monomer units selected from monomer units expressed by formula (Ia) and (Ib) (wherein R¹, R^a, R^b, R^c, R^d, R^e, R^f and R^g are each the same or different and express H or methyl; X¹, X², and X³ are each -CH₂- or -CO-O- and at least one of them expresses -CO-O-; m, p and q are each an integer of 0-2).



LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application]

BEST AVAILABLE COPY

Searching PAJ

converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

Copyright (C); 1998,2003 Japan Patent Office

BEST AVAILABLE COPY